

WEST Search History

DATE: Thursday, October 10, 2002

Set Name Query

side by side

Hit Count Set Name

result set

DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

| | | | |
|--|--|------|-----|
| L22 | L21 same (shak\$3 or agitat\$5) | 187 | L22 |
| L21 | ((photoresist or coat\$3 or wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same (soak\$3 or pre-soak\$3 or dip\$3) | 7106 | L21 |
| L20 | L19 same (shak\$3 or agitat\$5) | 9 | L20 |
| L19 | (photoresist or coat\$3)with (clean\$3 or rins\$3 or remov\$3 or treat\$3) with (soak\$3 or presoak\$3 or dip\$3) | 419 | L19 |
| L18 | L11 same (shak\$3 or agitat\$5) | 31 | L18 |
| L17 | L8 same (shak\$3 or agitat\$5) | 75 | L17 |
| L16 | L15 and agitat\$5 | 13 | L16 |
| L15 | l8 and DMSO | 35 | L15 |
| L14 | l8 and (DMSO with TMAH) | 0 | L14 |
| L13 | l8 same (DMSO with TMAH) | 0 | L13 |
| L12 | L11 same DMSO | 5 | L12 |
| L11 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with soak\$3 | 976 | L11 |
| L10 | ((wafer or substrate) adj\$3 (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with soak\$3 | 0 | L10 |
| L9 | l8 same (reciprocate\$3 or up and down) | 14 | L9 |
| L8 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same soak\$3 | 1666 | L8 |
| L7 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with soack\$3 | 0 | L7 |
| L6 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) with ((vat or tank or liquid) with heat\$3 with (electric\$3 or conduct\$3 or wire)) | 173 | L6 |
| L5 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with heat\$3 with (electric\$3 or conduct\$3 or wire)) | 239 | L5 |
| L4 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with (heat\$3 adj5 wire)) | 3 | L4 |
| L3 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with (heat\$3 adj5 electric\$3)) | 24 | L3 |
| L2 | ((wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3)) same ((vat or tank or liquid) with (heat\$3 adj5 electric)) | 9 | L2 |
| DB=USPT,JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ | | | |
| L1 | (wafer or substrate) with (clean\$3 or rins\$3 or remov\$3 or treat\$3) with (vat or tank or liquid) with (heat\$3 adj3 electric) | 3 | L1 |